

REMARKS

By this Office Action, the Examiner has required restriction to one of the following inventions under 35 U.S.C. §121:

- Group I: Claims 1-4, drawn to a colloidal silica composition, classified in class 516, subclass 81.
- Group II. Claims 5-8 and 10, drawn to methods of making colloidal silica, classified in class 516, subclass 86.
- Group III. Claim 9, drawn to a method of molding in a tube to make silica glass, classified in class 264, subclass 603.
- Group IV. Claims 10-14, drawn to a method of injection molding to make a silica glass, classified in class 264, subclass 478.

Response to the Requirement for Restriction, Applicants elect to prosecute the invention of Group II, Claims 5-8 and 10, drawn to methods of making colloidal silica, classified in class 516, subclass 86.

IN THE CLAIMS:

1. (Withdrawn)

2. (Withdrawn)

3. (Withdrawn)

4. (Withdrawn)

5. (Original) A method for producing a colloidal silica composition, the method comprising the steps of:

mixing and agitating an alkoxysilane compound, an organic solvent, deionized water, and a basic catalyst to produce colloidal silica;

washing the colloidal silica with deionized water to remove byproducts;

adding a basic organic material to the colloidal silica to adjust a hydrogen ion concentration (pH); and,

concentrating the pH-adjusted colloidal silica.

6. (Original) The method according to Claim 5, wherein the step of adding the basic organic material to adjust a hydrogen ion concentration is conducted before or after the step of washing the colloidal silica with deionized water to remove byproducts.

7. (Original) The method according to Claim 5, wherein the basic organic material is tetraethylammonium hydroxide.

8. (Original) The method according to Claim 5, wherein the basic catalyst is ammonia water.

9. (Withdrawn)

10. (Original) The method according to claim 5, further comprising the step of: applying a third heat treatment to remove organic materials.

11. (Withdrawn)

12. (Withdrawn)

13. (Withdrawn)

14. (Withdrawn)

15. (New) The method according to claim 5, wherein the basic organic material is added to the colloidal silica composition to the extent that the hydrogen ion concentration (pH) of colloidal silica becomes 12 or more.

16. (New) The method according to claim 5, wherein after concentrating the pH-adjusted colloidal silica, a concentration of the colloidal silica becomes 45% or more.

17. (New) The method according to Claim 5, wherein the basic organic material is added to the colloidal silica composition to the extent that the hydrogen ion concentration (pH) of colloidal silica becomes 12 to 12.8.

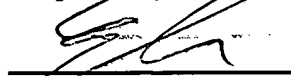
Application No. 10/607,156

Docket No. 5000-1-321

No fees are believed to be necessitated by the foregoing Response. However, should this be erroneous, authorization is hereby given to charge Deposit Account No. 502-470 for any underpayment, or credit any overages.

In view of the above, withdrawal of the Requirement for the Restriction and entry of the Preliminary Amendment are requested and an early action on the merits of the Claims is courteously solicited.

Respectfully submitted,



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